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**(71) Applicant(s):**

EASTMAN KODAK COMPANY [US/US]; 343 State Street Rochester, New York 14650-2201 (US) *(for all designated states except US)*

SCHULTZ, Terry Carl [US/US]; 39 North Avenue Hilton, New York 14468 (US) *(for US only)*

SHAW-KLEIN, Lori Jeanne [US/US]; 17 Riverside Street Rochester, New York 14613 (US) *(for US only)*

NICHOLAS, Thomas Peter [US/US]; 143 Southern Parkway Rochester, New York 14618 (US) *(for US only)*

RUSCHAK, Kenneth J. [US/US]; 236 Wimbledon Road Rochester, New York 14617 (US) *(for US only)*

**(72) Inventor(s):**

SCHULTZ, Terry Carl; 39 North Avenue Hilton, New York 14468 (US)

SHAW-KLEIN, Lori Jeanne; 17 Riverside Street Rochester, New York 14613 (US)

NICHOLAS, Thomas Peter; 143 Southern Parkway Rochester, New York 14618 (US)

RUSCHAK, Kenneth J.; 236 Wimbledon Road Rochester, New York 14617 (US)

**(74) Common Representative(s):**

EASTMAN KODAK COMPANY; 343 State Street Rochester, New York 14650-2201 (US)

**(54) Title (EN):** INKJET RECORDING ELEMENT

**(54) Title (FR):** élément D'ENREGISTREMENT À JET D'ENCRE

**(57) Abstract:**

**(EN):** An inkjet recording element comprising an absorbent support, a porous base layer nearest the support, a porous ink-receiving intermediate layer above the base layer, and a porous ink-receiving upper layer above the intermediate layer. The base layer and intermediate layers are each present in an amount of at least 25 g/m<sup>2</sup> and the total dry weight coverage of the base layer, the intermediate layer, and the upper layer is 60 to 130 g/m<sup>2</sup> in order to handle high fluxes of ink compositions during printing and to provide high gloss upon calendering. Also disclosed is an advantageous method of making such inkjet recording materials.

**(FR):** L'invention concerne un élément d'enregistrement à jet d'encre comprenant un support absorbant, une couche de base poreuse, qui est la couche la plus proche du support, une couche intermédiaire poreuse recevant l'encre au-dessus de la couche de base, et une couche supérieure poreuse recevant l'encre au-dessus de la couche intermédiaire. La couche de base et les couches intermédiaires sont chacune présentes dans une quantité d'au moins 25 g/m<sup>2</sup> et la couverture du poids sec total de la couche de base, de la couche intermédiaire, et de la couche supérieure est comprise entre 60 et 130 g/m<sup>2</sup> afin de gérer des flux importants de compositions d'encre pendant l'impression et d'assurer un brillant élevé lors du calandrage. L'invention concerne également un procédé avantageux de fabrication de tels matériaux d'enregistrement à jet d'encre.

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